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## REMARKS

In response to the action, Applicants have cancelled claims 1 to 10 and submitted claims 11 to 20 for consideration. Applicants respectfully request reconsideration in view of the following remarks.

Newly submitted claims 11 to 20 correspond to original-filed claims 1 to 10 with several modification. First, claim 1 includes the composition limitation of original-filed claim 4. Second, claims 14 and 19 include limitations to carbon doped oxide. The specification at paragraph 12, lines 9 and 10 provide a basis for the limitation. Third, claim 18 includes the clause "stopping the polishing before removing all of the silicon carbide-nitride layer" from original claim 8. Finally, claim 20 includes the pH range of 7 to 10. The specification at paragraph 20, lines 2 and 3 provides a basis for the limitation. Applicants respectfully submit that the amendments enter no new matter.

Applicants elected group 1 claims 1 to 7 without traverse. In response to the action, however, Applicants further added method limitations to the composition of claim 4 (newly submitted claim 1). The method claim structure clarifies that the functional language serves to polish wafers having silicon nitride and silicon carbide-nitride layers. In view of the incorporation of the composition claims into a method format, Applicants respectfully request consideration of newly submitted claims 11 to 20.

The action rejects claim 1 to 4 and 7 under 35 U.S.C. § 102(c) as being anticipated by US Pat. Pub. No. 2003/0102457 to Miller. In particular, the rejection included an inherency argument with respect to the nonionic surfactant. The amended claims now include the particular nonionic surfactants--alkanoamide, alkyl polyethylene oxide, alkylphenol polyethylene oxide and a mixture thercof--that are effective for silicon nitride/silicon carbidenitride selectivity. Applicants respectfully submit that since Miller fails to disclose or suggest the use of alkanoamide, alkyl polyethylene oxide, alkylphenol polyethylene oxide and a mixture thereof for silicon nitride/silicon carbide-nitride selectivity, newly submitted claims 11 to 20 are not anticipated or obvious in view of the cited art.

Please call Applicants' Attorney at 302-283-2136 if a call would expedite further handling of this applications.

Respectfully submitted,

2-15-05

Date

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